

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Ismail Kashkoush

Examiner: Lan Vinh

Serial No.: 10/585,229

Art Unit: 1713

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For: **SYSTEM AND METHOD FOR
SELECTIVE ETCHING OF SILICON
NITRIDE DURING SUBSTRATE
PROCESSING**

Attorney Docket No.: AKR-034-US

RESPONSE TO RESTRICTION REQUIREMENT

In response to the restriction requirement dated September 3, 2010, Applicant hereby elects without traverse Group I, which is drawn to a method for selective etching of silicon nitride during substrate processing and encompasses claims 1-12 and 22.

The Belles Group, P.C.

Date: October 4, 2010



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